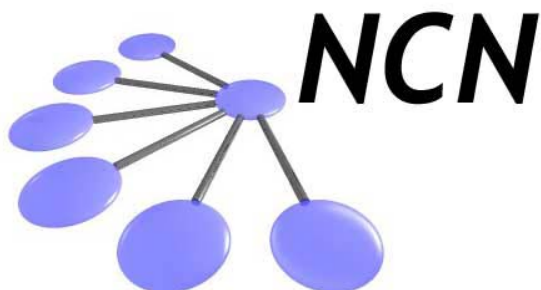


Network for Computational Nanotechnology (NCN)

Berkeley, Univ. of Illinois, Norfolk State, Northwestern, Purdue, UTEP

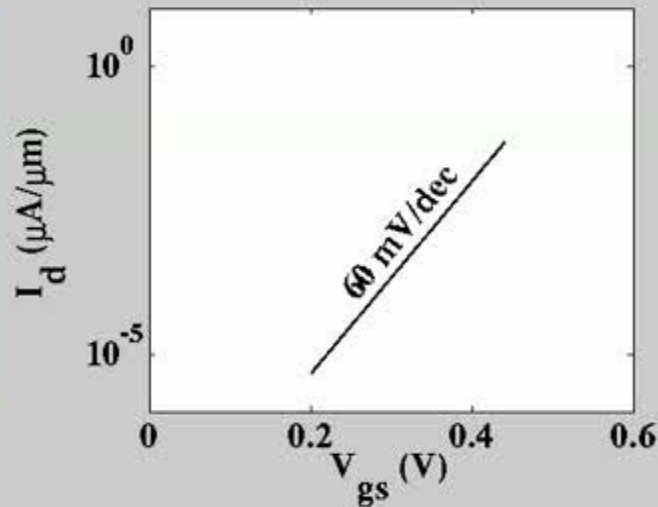
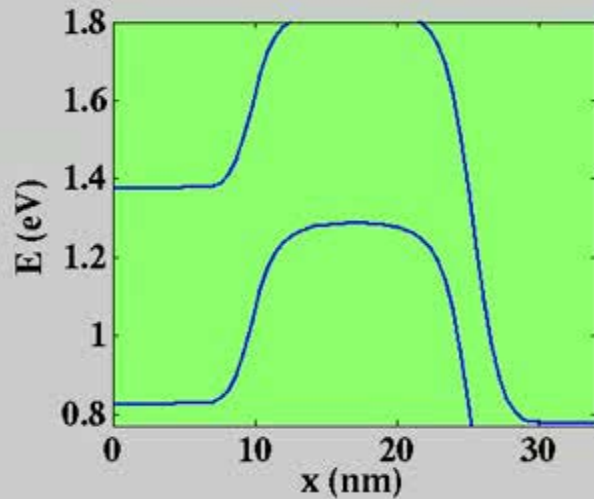
Performance Limitations of Graphene Nanoribbon Tunneling FETS due to Line Edge Roughness

Mathieu Luisier and Gerhard Klimeck

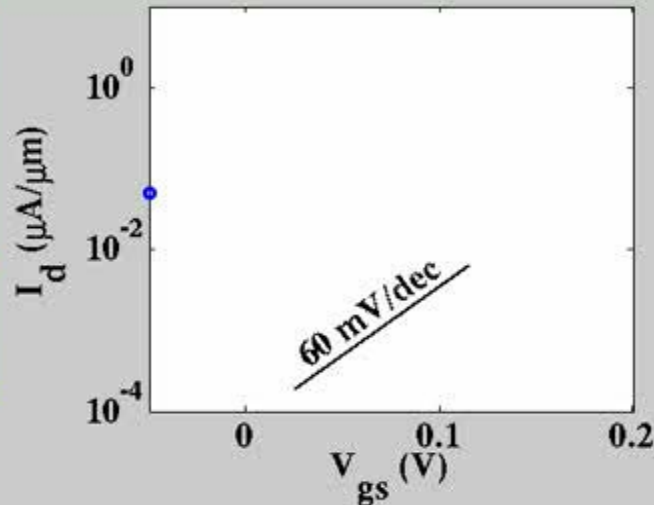
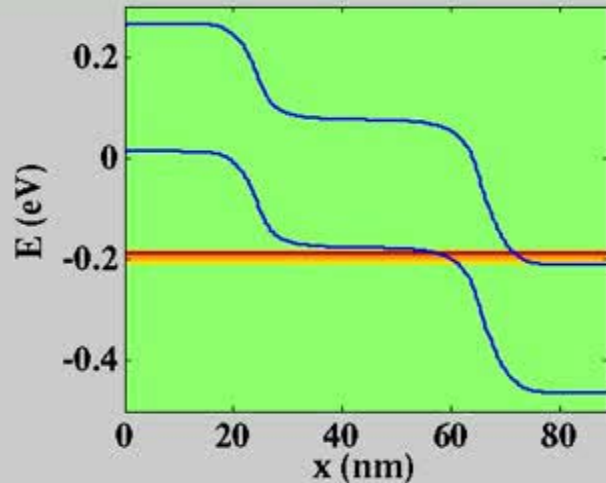


PURDUE
UNIVERSITY

Tunneling Transistor after MOSFET?



**MOSFET:
Thermionic
Current**



**TFET:
B-to-B Tunn.
Current**

Graphene Nanoribbon TFETs

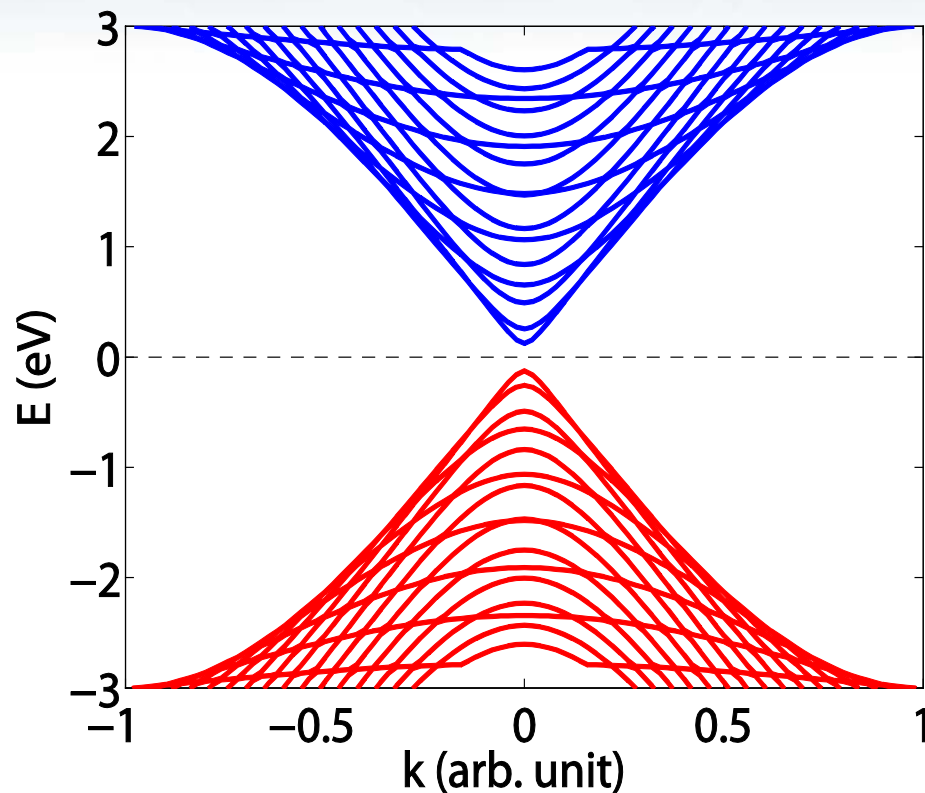
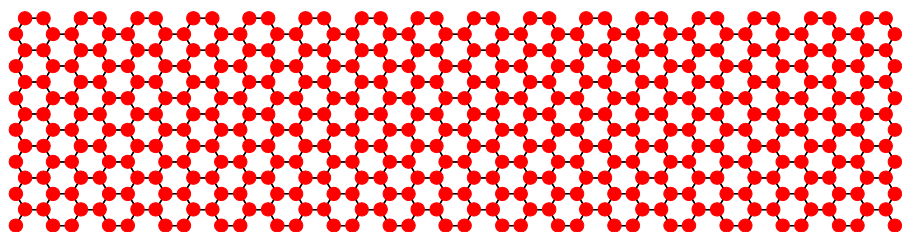
Graphene Nanoribbon:

GOOD:

- One-Dimensional Structure
- Compatible to Planar Tech.
- Low Effective Masses
- Tunable Band Gap (Width)

BAD:

- Band Gap => Narrow Ribbon
- Edges => Roughness



Bandstructure of 5.1nm GNR
Symmetric **CB** and **VB**
Band Gap $E_g = 0.251$ eV

- **Introduction**
- **Physical Models**
 - Bandstructure and Transport Models**
- **Ideal Graphene Nanoribbon**
 - Structure Definition and Optimization**
 - Transfer Characteristics**
- **Line Edge Roughness**
 - Roughness Generation**
 - Band Gap Reduction**
 - Performance Deterioration**
- **Conclusion and Outlook**

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Bandstructure Model

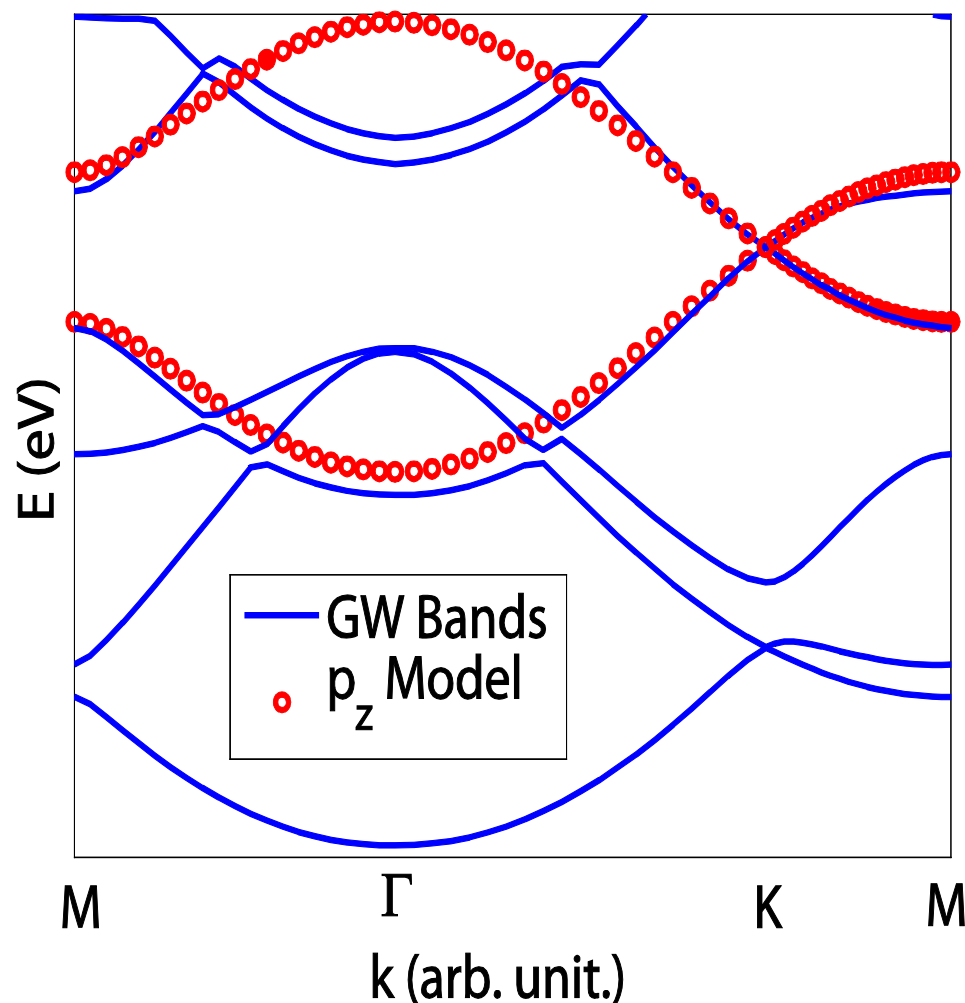
Nearest-Neighbor p_z Tight-Binding Method

GOOD:

- one single parameter $V_{pp\pi}$
- HOMO and LUMO bands
- *atomistic* description
- computationally efficient

BAD:

- not really full-band

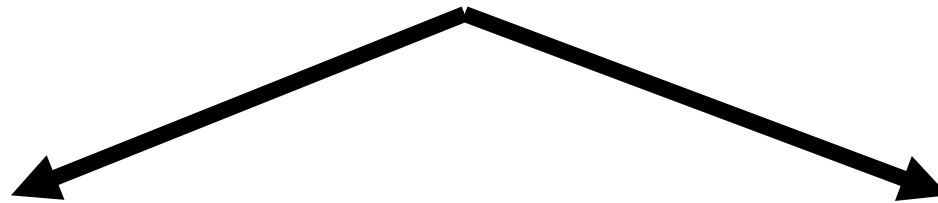


Quasi 3D Schrödinger Equation

$$\mathbf{H} | \psi_E \rangle = E | \psi_E \rangle$$

Tight-Binding Ansatz for the Wave Function

$$\langle \mathbf{r} | \psi_E \rangle = \sum_{ijk} C_{ijk}(E) \phi(\mathbf{r} - \mathbf{R}_{ijk})$$



$$(\mathbf{E} - \mathbf{H} - \Sigma) \cdot \mathbf{G}^R = \mathbf{I}$$

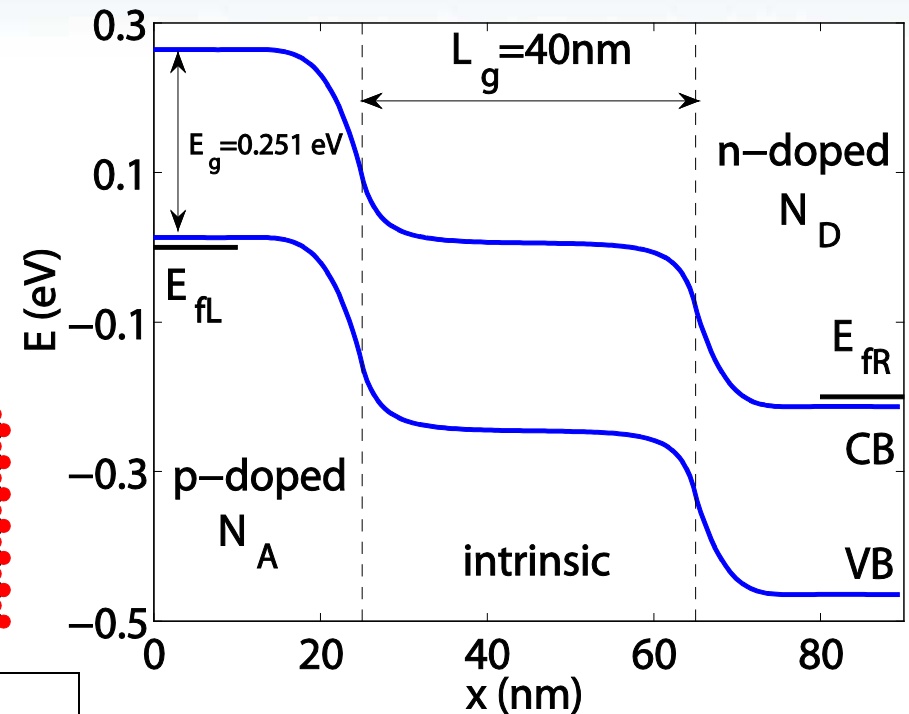
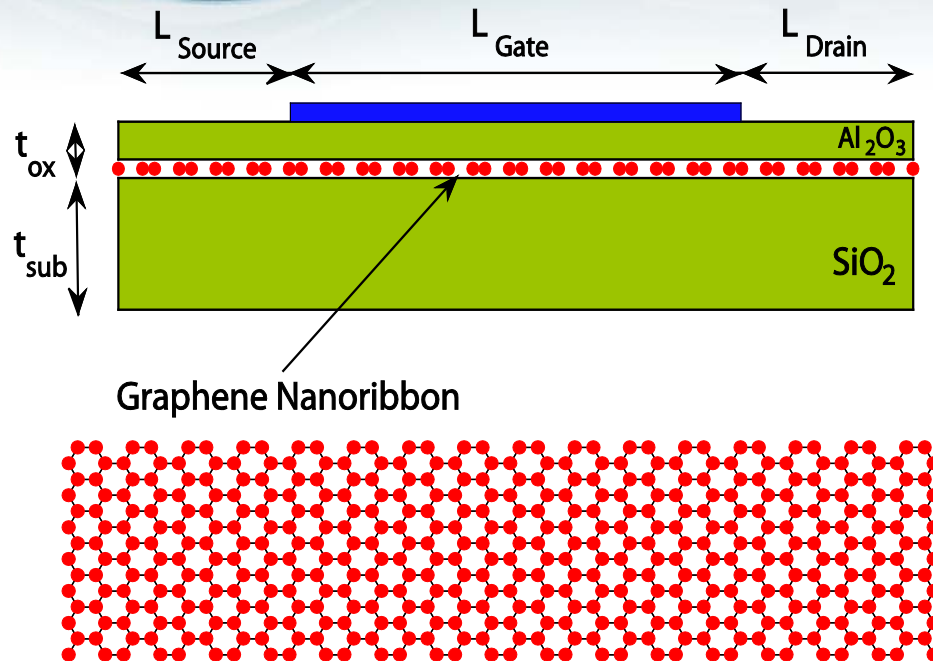
Matrix Inversion Problem

$$(\mathbf{E} - \mathbf{H} - \Sigma) \cdot \mathbf{C} = \mathbf{I} n_j$$

Linear System of Eq.

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Graphene Nanoribbon with Armchair Edges

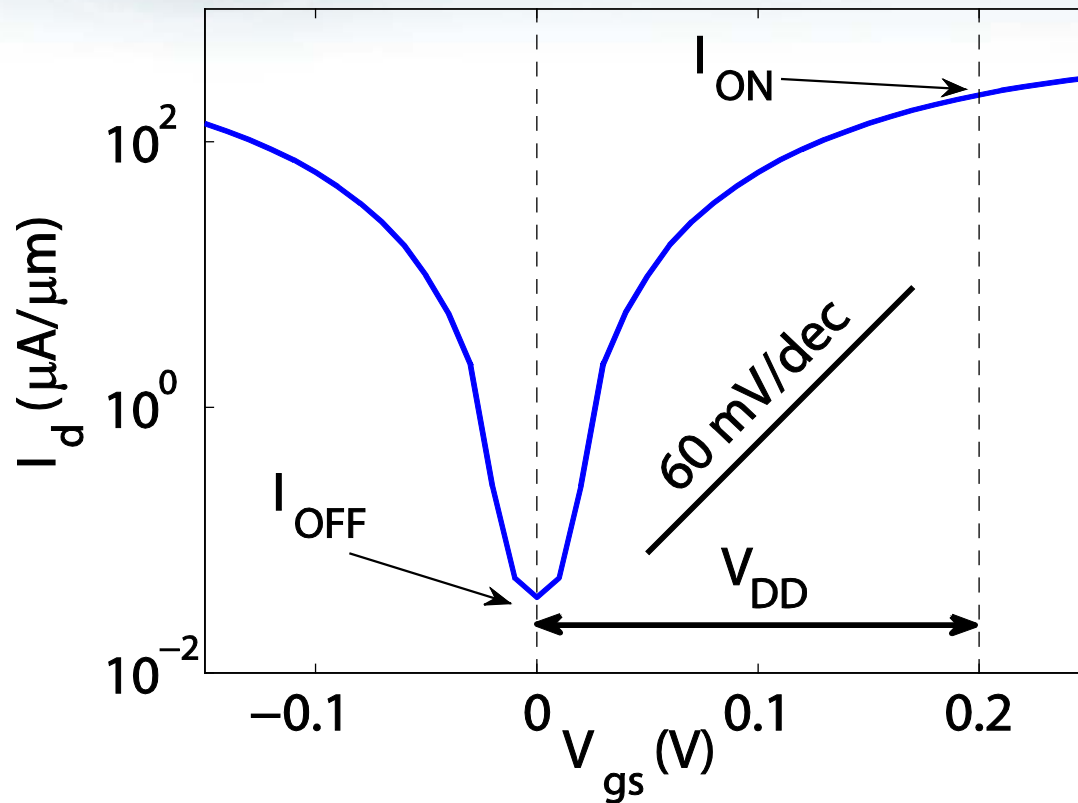


TFET p-i-n Structure:

- 5.1nm GNR Deposited on SiO_2 ($N=21$)
- 1nm EOT (2.35nm Al_2O_3 with $\epsilon_R=9.1$)
- 40nm Gate Length
- 25nm Source and Drain Extensions

- Supply Voltage $V_{\text{DD}}=0.2\text{ V}$
- Symmetric Doping Conc.
- GNR Band Gap $E_g=0.251\text{ eV}$

I_d - V_{gs} Transfer Characteristics



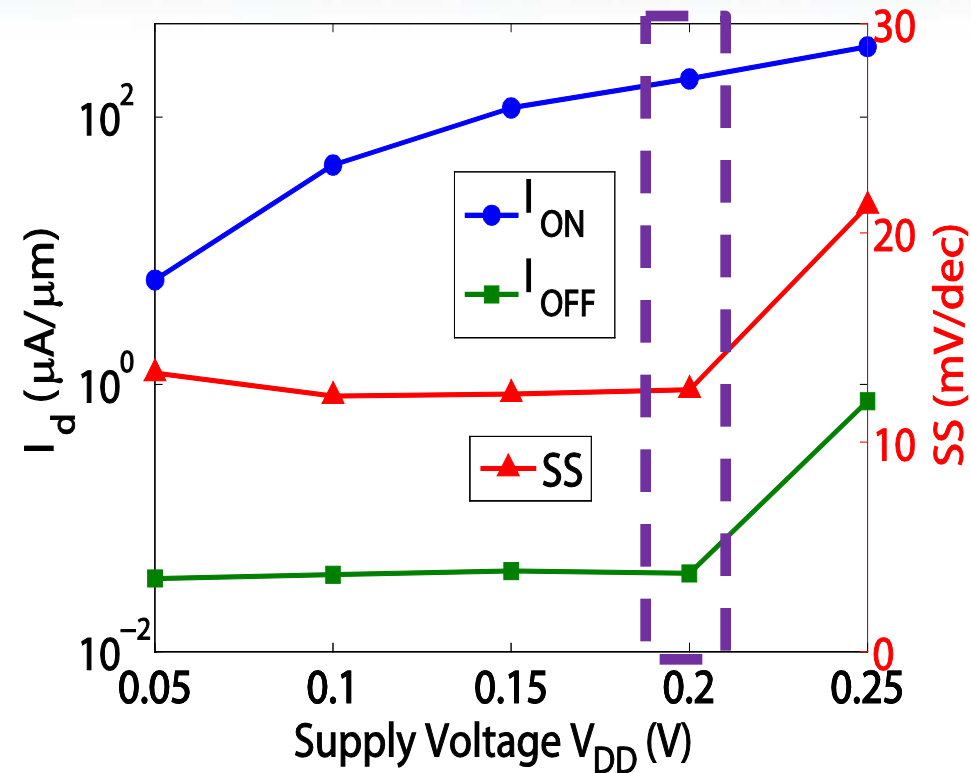
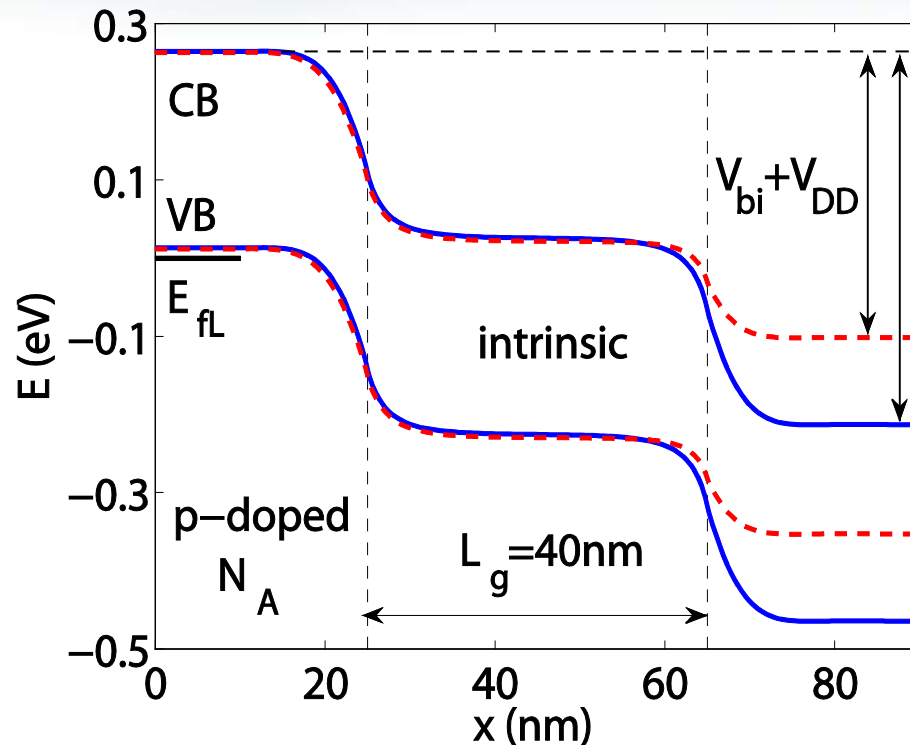
ON-Current:
 $I_{\text{ON}} = 225 \mu\text{A}/\mu\text{m}$

OFF-Current:
 $I_{\text{OFF}} = 37 \text{ nA}/\mu\text{m}$

Subthreshold Slope
 $SS = 12 \text{ mV/dec}$

- 1) How can we decrease the OFF-Current?
- 2) How can we increase the ON-Current?

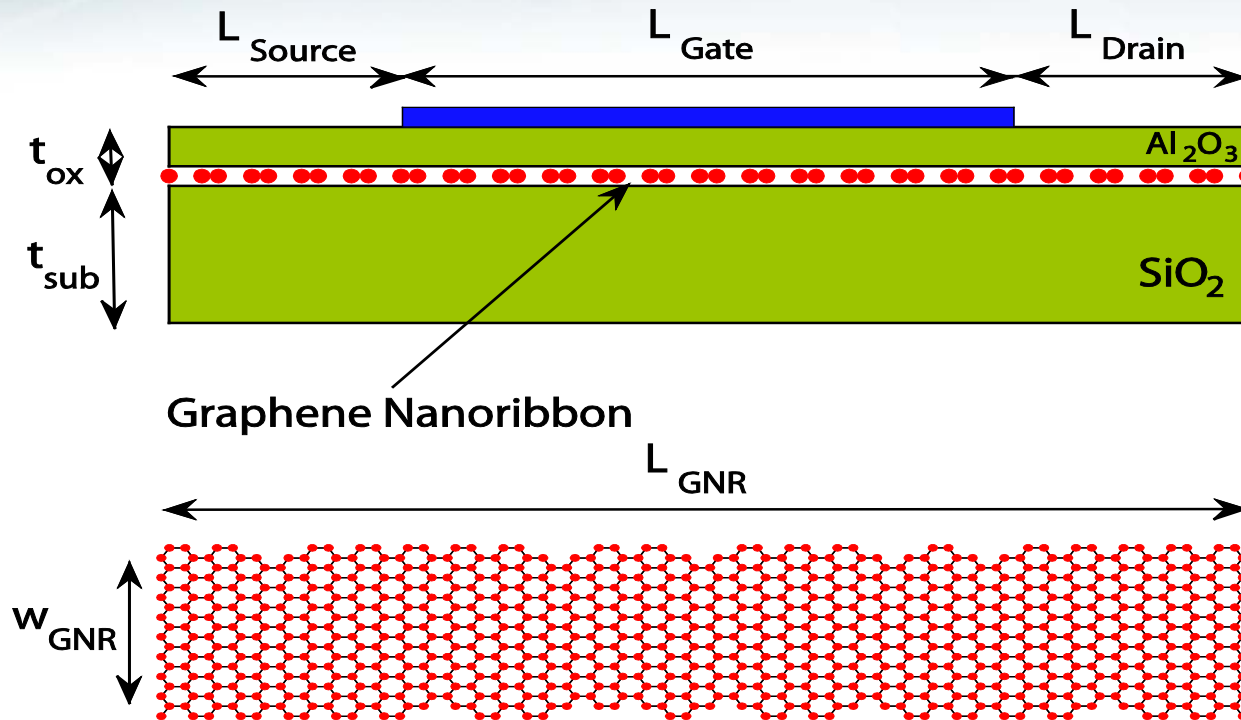
Determination of Supply Voltage



- ON-Current Increases with V_{DD} (due to Gate Voltage)
- Condition $V_{bi} + V_{DD} < 2 * E_g$ must be Satisfied
- Condition Broken \Rightarrow Ambipolar Channel Behavior

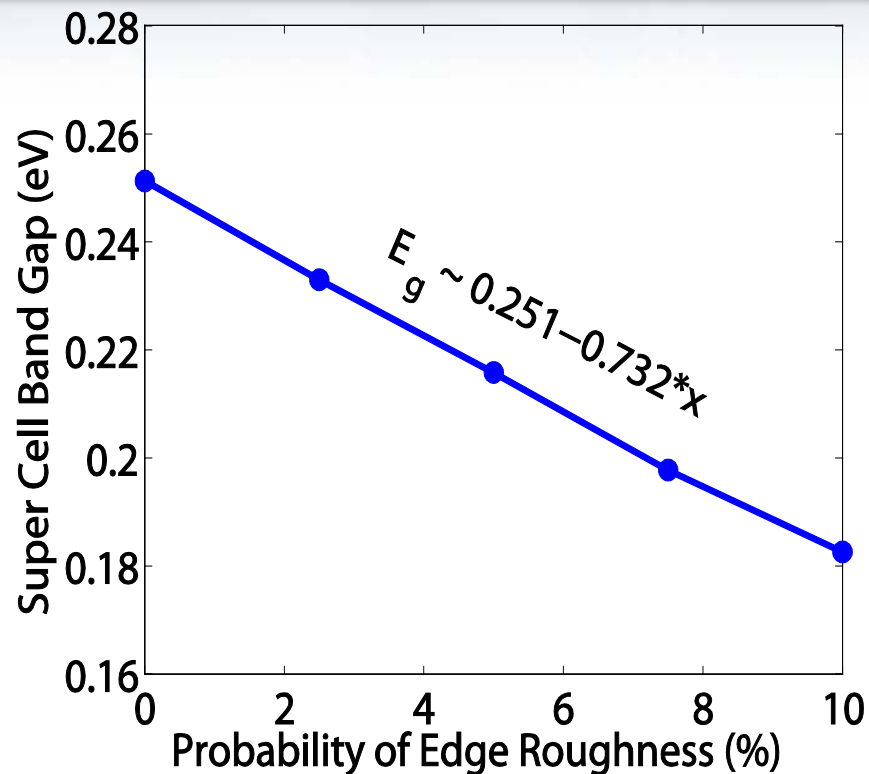
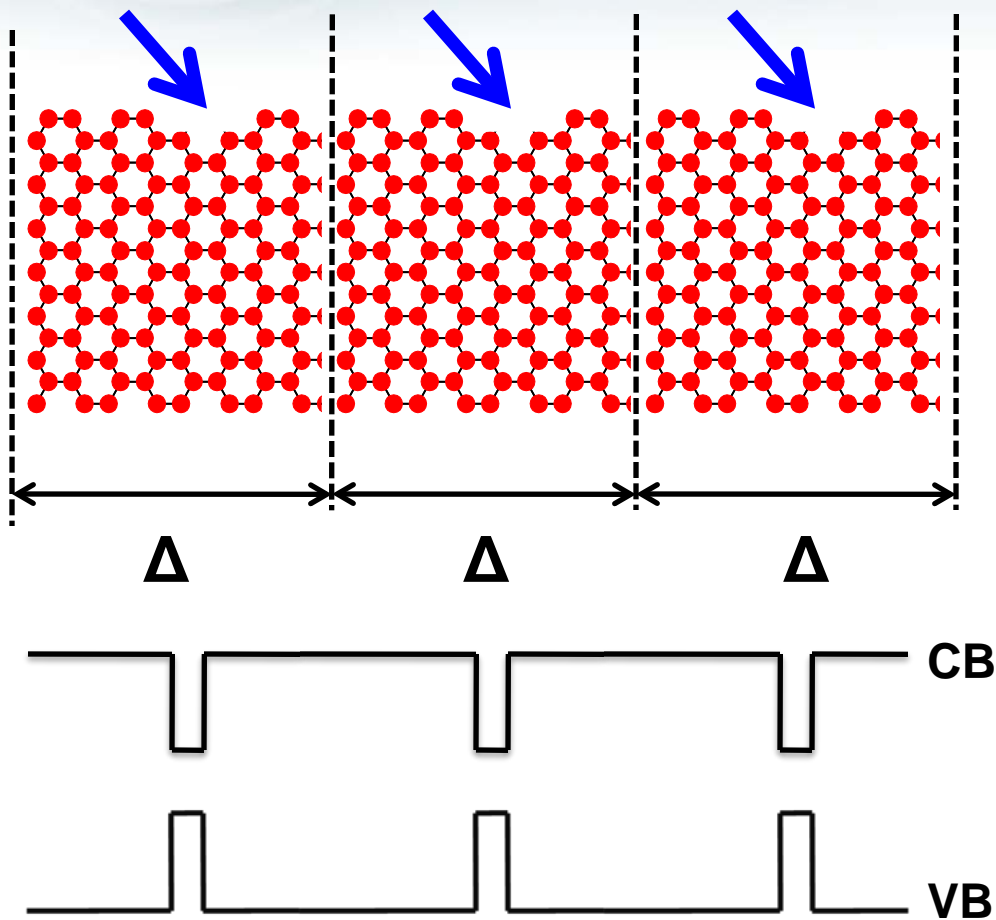
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Structure Definition



- No Perfect Edges => Line Edge Roughness (LER) Scattering
- Simple Roughness Model: Remove Pair of Atoms with Probability P
- Random Distribution of Removed Atoms: $N=21$ to $N=20$

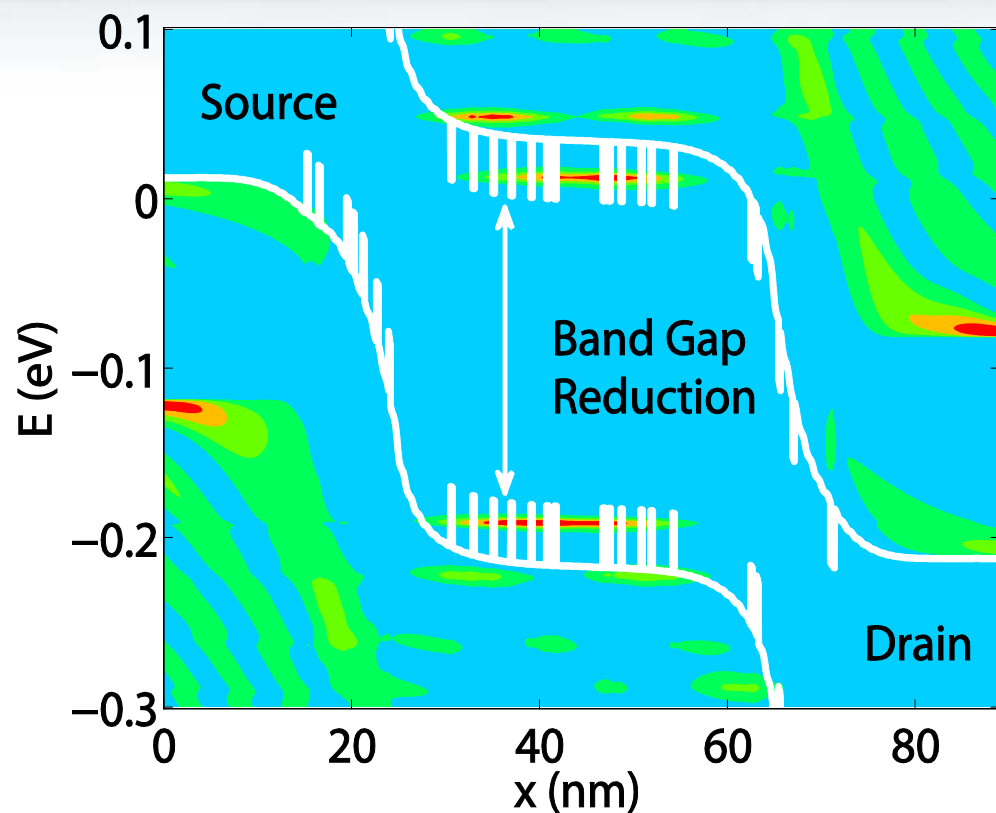
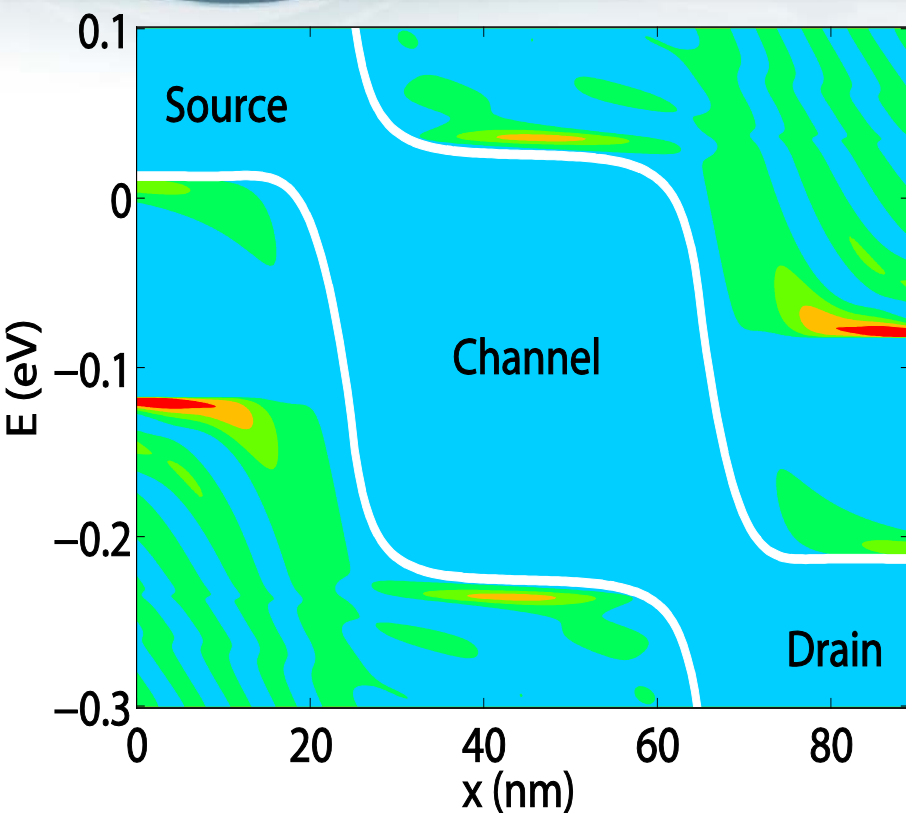
Band Gap Reduction



Edge Defect => Symmetry Broken
Band Gap Reduction
~Linear Dependence on P

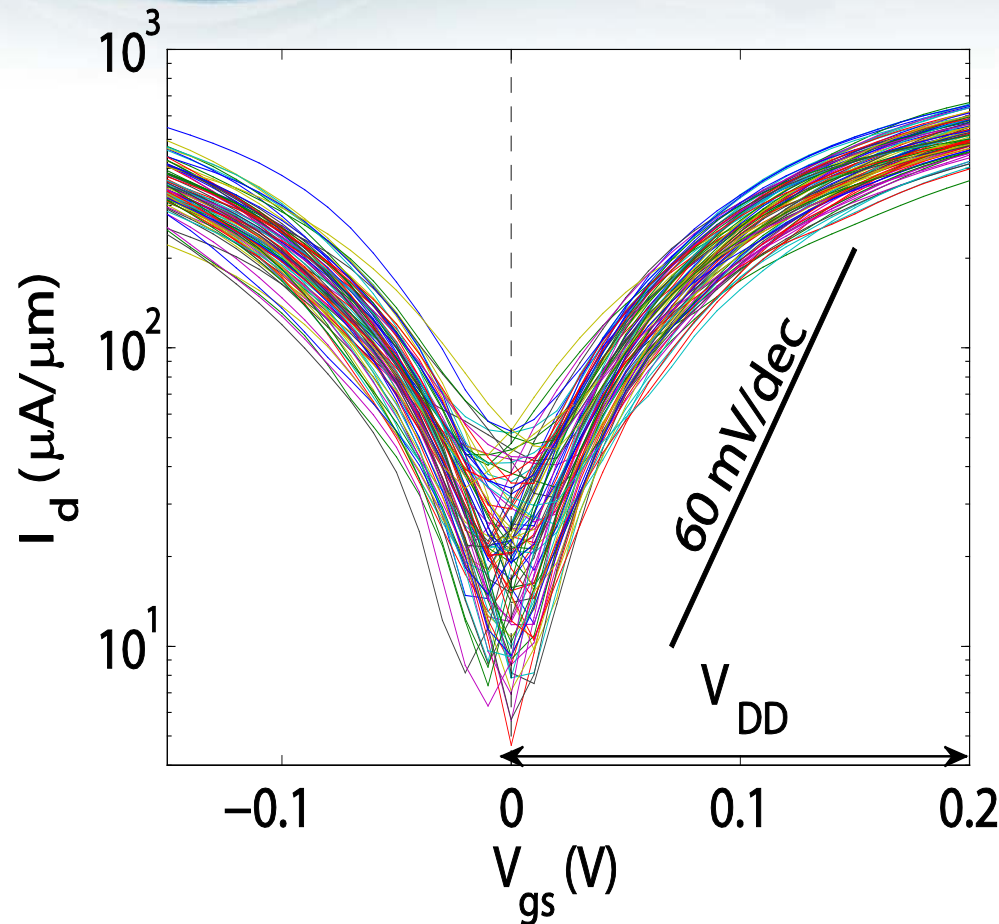
Periodic Structure with 1 Defect/Period

GNR Density-of-States



- Spectral Density-of-States Around the Intrinsic Channel w and w/o LER
- Band Gap Reduction => Superlattice Structure => BG Localized States
- Localized States => Increased B-to-B Tunneling Probabilities

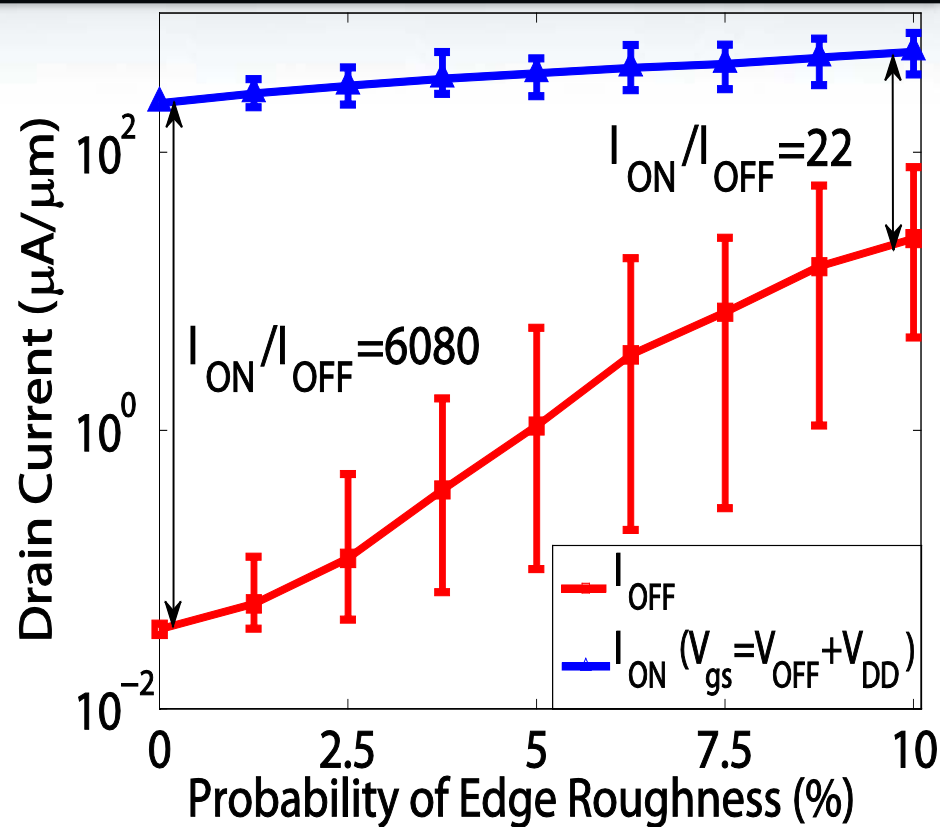
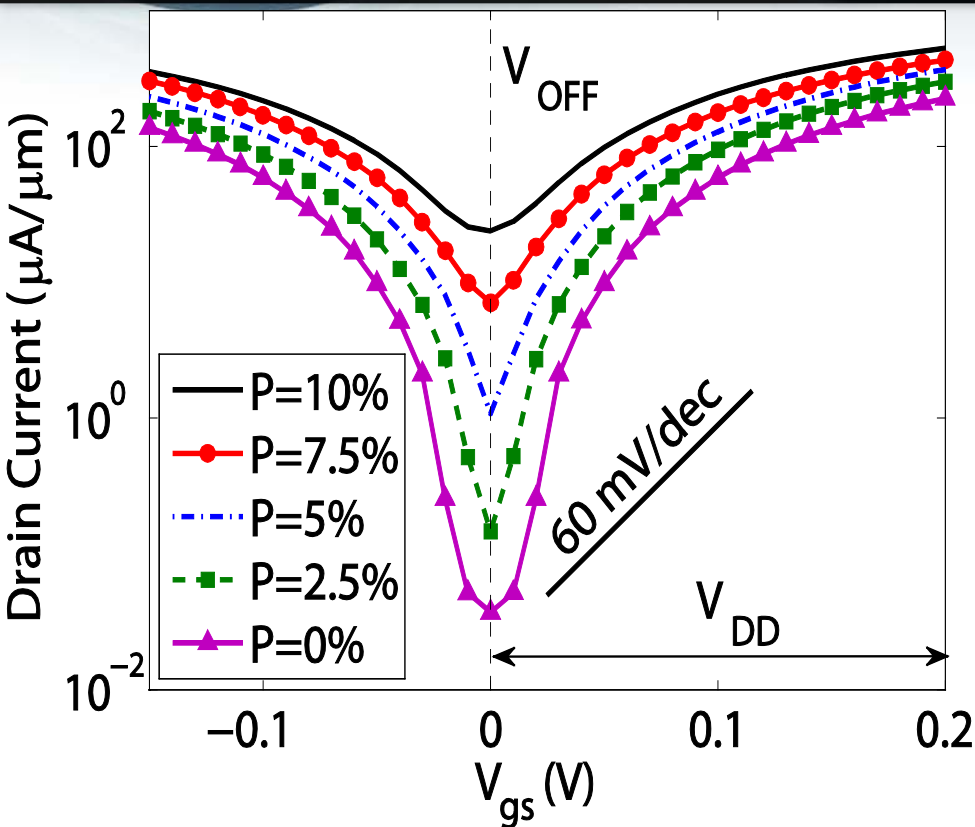
Multiple Random Samples Generation



- Roughness Probability P from 0 to 10%
- Statistical Sampling of LER (100 Samples per Roughness Probability)
- All Devices Different
- Need: Average ON- and OFF-Currents, Standard Deviations, and Max and Min Values

**Graphene Nanoribbon TFETs with 10% of Edge Atoms Removed
=> Strong Variation of ON- and OFF-Currents, Poor Performances**

Transfer Characteristics and I_{ON}/I_{OFF} Ratio



- Comparison of GNR TFETs with Different LER Probabilities
- Strong Deterioration of Most Device Performances
- Better Control of Edges or Better Structure Optimization

Conclusion and Outlook

• GNR TFET Simulation

p_z Tight-Binding Orbital Model
3D Schrödinger-Poisson Solver

• Device Simulation

Structure Optimization (Doping, L_g , V_{DD})

LER \Rightarrow Localized Band Gap States

LER \Rightarrow Performance Deterioration

• Outlook and Challenges

Ripples Scattering

More Accurate Bandstructure Model

Dissipative Scattering (EI-Ph)

